

This Page Is Inserted by IFW Operations
and is not a part of the Official Record

BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images may include (but are not limited to):

- BLACK BORDERS
- TEXT CUT OFF AT TOP, BOTTOM OR SIDES
- FADED TEXT
- ILLEGIBLE TEXT
- SKEWED/SLANTED IMAGES
- COLORED PHOTOS
- BLACK OR VERY BLACK AND WHITE DARK PHOTOS
- GRAY SCALE DOCUMENTS

IMAGES ARE BEST AVAILABLE COPY.

**As rescanning documents *will not* correct images,
please do not report the images to the
Image Problem Mailbox.**

PATENT COOPERATION TREATY

PCT

NOTIFICATION OF THE RECORDING
OF A CHANGE(PCT Rule 92bis.1 and
Administrative Instructions, Section 422)Date of mailing (day/month/year)
24 April 2002 (24.04.02)

From the INTERNATIONAL BUREAU

To:

YOU ME PATENT & LAW FIRM
Teheran Bldg., 825-33
Yoksam-dong
Kangnam-ku
Seoul 135-080
RÉPUBLIQUE DE CORÉEApplicant's or agent's file reference
OPPO10704KR

IMPORTANT NOTIFICATION

International application No.
PCT/KR01/01391International filing date (day/month/year)
16 August 2001 (16.08.01)

1. The following indications appeared on record concerning:

 the applicant the inventor the agent the common representative

Name and Address

KWON, Young-Woo
CHEON, Chang-Yul
KIM, Yong-Kweon
SONG, Seung-Hyun
BAEK, Chang-Wook
LEE, Yang-Soo

State of Nationality

KR

State of Residence

KR

Telephone No.

Facsimile No.

Teleprinter No.

2. The International Bureau hereby notifies the applicant that the following change has been recorded concerning:

 the person the name the address the nationality the residence

Name and Address

REPBULIC OF KOREA
(THE PRESIDENT OF SEOUL NATIONAL
UNIVERSITY)
San 56-1
Shillim 1-dong
Kwanak-Ku
Seoul 151-011
Republic of Korea

State of Nationality

KR

State of Residence

KR

Telephone No.

Facsimile No.

Teleprinter No.

3. Further observations, if necessary:

The persons in Box 1 are applicants/ inventor for US only. Additional applicant in Box 2
is applicant for all designated states except US.

4. A copy of this notification has been sent to:

 the receiving Office

 the designated Offices concerned

 the International Searching Authority

 the elected Offices concerned

 the International Preliminary Examining Authority

 other:
The International Bureau of WIPO
34, chemin des Colombettes
1211 Geneva 20, Switzerland

Authorized officer

Lazar Joseph PANAKAL

Facsimile No.: (41-22) 740.14.35

Telephone No.: (41-22) 338.83.38

PCT COOPERATION TREATY

PCT

NOTIFICATION OF THE RECORDING
OF A CHANGE(PCT Rule 92bis.1 and
Administrative Instructions, Section 422)

Date of mailing (day/month/year) 25 avril 2002 (25.04.02)	From the INTERNATIONAL BUREAU To: YOU ME PATENT & LAW FIRM Teheran Bldg., 825-33 Yoksam-dong Kangnam-ku Seoul 135-080 RÉPUBLIQUE DE CORÉE
Applicant's or agent's file reference OPP010704KR	IMPORTANT NOTIFICATION
International application No. PCT/KR01/01391	International filing date (day/month/year) 16 août 2001 (16.08.01)

1. The following indications appeared on record concerning:

the applicant the inventor the agent the common representative

Name and Address KWON, Young-Woo CHEON, Chang-Yul KIM, Yong-Kweon SONG, Seung-Hyun BAEK, Chang-Wook LEE, Yang-Soo	State of Nationality KR	State of Residence KR
	Telephone No.	
	Facsimile No.	
	Teleprinter No.	

2. The International Bureau hereby notifies the applicant that the following change has been recorded concerning:

the person the name the address the nationality the residence

Name and Address REPUBLIC OF KOREA (THE PRESIDENT OF SEOUL NATIONAL UNIVERSITY) San 56-1 Shillim 1-dong Kwanak-Ku Seoul 151-011 Republic of Korea	State of Nationality KR	State of Residence KR
	Telephone No.	
	Facsimile No.	
	Teleprinter No.	

3. Further observations, if necessary:

The applicant's in Box 1 remain designated for the US only and the additional applicant is designated for all states except the US.

4. A copy of this notification has been sent to:

<input checked="" type="checkbox"/> the receiving Office	<input checked="" type="checkbox"/> the designated Offices concerned
<input type="checkbox"/> the International Searching Authority	<input type="checkbox"/> the elected Offices concerned
<input type="checkbox"/> the International Preliminary Examining Authority	<input type="checkbox"/> other:

The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland Facsimile No.: (41-22) 740.14.35	Authorized officer Lazar Joseph PANAKAL Telephone No.: (41-22) 338.83.38
---	--

PATENT COOPERATION TREATY

10/18280
5000
PCT

NOTIFICATION OF ELECTION

(PCT Rule 61.2)

From the INTERNATIONAL BUREAU

To:

Commissioner
 US Department of Commerce
 United States Patent and Trademark
 Office, PCT
 2011 South Clark Place Room
 CP2/5C24
 Arlington, VA 22202
 ETATS-UNIS D'AMERIQUE

in its capacity as elected Office

RECEIVED
 TUE 18 AUG 2003
 1000 MAIL ROOM

Date of mailing (day/month/year) 15 August 2002 (15.08.02)	To:
International application No. PCT/KR01/01391	Commissioner US Department of Commerce United States Patent and Trademark Office, PCT 2011 South Clark Place Room CP2/5C24 Arlington, VA 22202 ETATS-UNIS D'AMERIQUE
International filing date (day/month/year) 16 August 2001 (16.08.01)	Priority date (day/month/year) 17 August 2000 (17.08.00)
Applicant KWON, Young-Woo et al	

1. The designated Office is hereby notified of its election made:

 in the demand filed with the International Preliminary Examining Authority on:

18 March 2002 (18.03.02)

 in a notice effecting later election filed with the International Bureau on:2. The election was was not

made before the expiration of 19 months from the priority date or, where Rule 32 applies, within the time limit under Rule 32.2(b).

The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland Facsimile No.: (41-22) 740.14.35	Authorized officer Farid ABOU Telephone No.: (41-22) 338.83.38
---	--

(19) World Intellectual Property Organization
 International Bureau



(43) International Publication Date
 21 February 2002 (21.02.2002)

PCT

(10) International Publication Number
WO 02/15327 A1

(51) International Patent Classification⁷: **H01Q 3/26**

100-456 Seoul (KR). **BAEK, Chang-Wook** [KR/KR]; Indukwon Apt. 108-702, Kwanyang 2-dong, Dongan-ku, Anyang-city, Kyungki-do 431-062 (KR). **LEE, Yang-Soo** [KR/KR]; 412-359, Shinrim 1-dong, Kwanak-ku, Seoul 151-011 (KR).

(21) International Application Number: **PCT/KR01/01391**

(22) International Filing Date: 16 August 2001 (16.08.2001)

(25) Filing Language:

Korean

(74) Agent: **YOU ME PATENT & LAW FIRM**; Teheran Bldg., 825-33, Yoksam-dong, Kangnam-ku, Seoul 135-080 (KR).

(26) Publication Language:

English

(30) Priority Data:

2000/47534 17 August 2000 (17.08.2000) KR

(81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW.

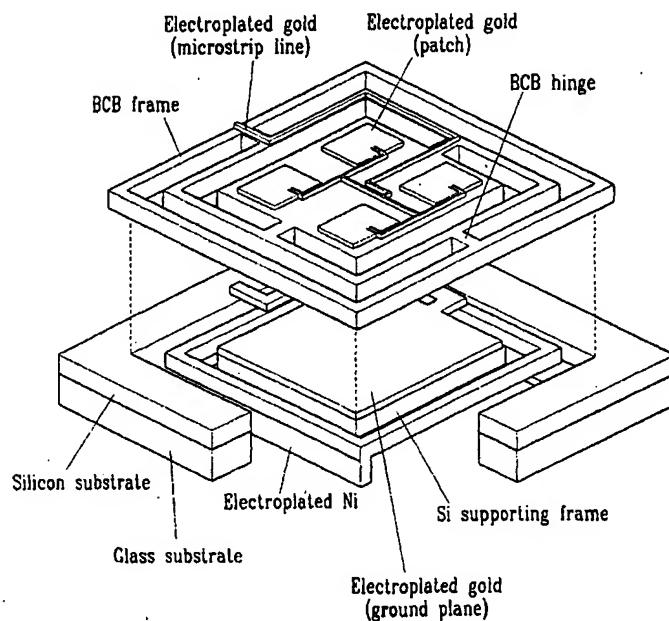
(71) Applicants and

(72) Inventors: **KWON, Young-Woo** [KR/KR]; Samik Apt. 123-902, Sunae-dong, Bundang-ku, Sungnam-city, Kyungki-do 463-020 (KR). **CHEON, Chang-Yul** [KR/KR]; Daekyo Apt. 2-706, Yeouido-dong, Youngdeunpo-ku, Seoul 150-010 (KR). **KIM, Yong-Kweon** [KR/KR]; Chungdam Villa C-dong 3, Chungdam-dong 95, Kangnam-ku, Seoul 135-100 (KR).

(84) Designated States (regional): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

[Continued on next page]

(54) Title: A MECHANICAL BEAM STEERING ANTENNA AND A FABRICATION METHOD THEREOF



(57) Abstract: The present invention is concerning an element antenna to construct an efficient antenna system, which is able to control mechanical movement of micro-strip patch antenna and to control electrical phase of signal. The movement of an element antenna is come from movement of a platform on which the element antenna is formed. The platform is made of dielectric material and able to move independently from base. The element antenna can be controlled to any direction. An antenna patch has magnetic material layer such as nickel on the backside. The antenna patch is driven by magnetic force.

WO 02/15327 A1

**Published:**

- *with international search report*
- *before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments*

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

A Mechanical Beam Steering Antenna and A Fabrication Method thereof

BACKGROUND OF THE INVENTION

5 (a) Field of the Invention

The present invention relates to an array antenna system.

(b) Description of the Related Art

Conventional array antenna systems are used to send beams in desired directions, that is, in the directions to which targets are located. The 10 directions of the beams of the array antenna are steered by controlling electrical phase differences between respective antennas that form an array. This technique enables antenna beams to be sent in a direction where a target object is located without rotating the antenna, or enables antenna beams to be received from that direction so that the direction of the target 15 that sends or reflects the signals can be effectively caught.

FIG. 1 shows an array antenna system where "d" represents a distance between the antennas, " ϕ " represents an electric phase of the antennas, and " θ " represents the direction of the beams to be sent.

However, this array antenna system is problematic in that the 20 performance of the corresponding antenna is reduced when the direction of the beams digresses from the central axis of the individual antennas. The array antenna's radiation pattern is represented by a multiplication of the respective antennas' radiation patterns by an array factor. The array factor

can only be adjusted by using electrical phase differences between the antennas. When the direction of the beams digress from of the central axis, the amount of the energy radiating from each antenna is reduced compared to the that of the maximum energy, and the array factor is multiplied to the energy so that the antenna performance is reduced.

To solve this, antennas are pre-configured to decline in various directions, and antennas that decline in the desired direction of the beams are selected using a switch so that the array antenna system, including the antennas can be used. However, this method increases cost because of the increase of the number of the antennas, the magnitude of the array antenna is increased, and also, limited beam angles can be selected.

SUMMARY OF THE INVENTION

It is an object of the present invention to provide an antenna for building an array antenna system for obtaining uniform maximum performance in all beam directions by overcoming the problem that lowers the performance of a conventional array system when the angle between the beam direction of the array system and the central axis of each unit antenna is increased.

It is another object of the present invention to provide a small-size antenna for enabling fast mechanical motion and minute control of the driving angle.

It is still another object of the present invention to mass manufacture antenna array systems capable of mechanical operation through a batch process and integrate antennas and drivers.

In one aspect of the present invention, an antenna device comprises:

5 an antenna; a first rotation shaft for enabling angular displacements of the antenna in the first direction; a second rotation shaft for enabling angular displacements of the antenna in the second direction independent from the angular displacements of the antenna in the first direction; a platform for supporting the antenna; an internal frame connected to the platform through

10 the first rotation shaft; an external frame connected to the platform through the second rotation shaft; a ground plane formed on a surface opposite to a surface on which the antenna of the platform is formed; a first conductive line connected to the antenna; a second conductive line connected to the ground plane; and a driver for mechanically displacing the platform and the internal

15 frame using electromagnetic force.

In another aspect of the present invention, a method for manufacturing an antenna device comprises: attaching a silicon substrate to a glass substrate; processing the glass substrate to form a displacement space; forming a ground plane on the silicon substrate; forming a dielectric layer on the ground plane; forming an antenna on the dielectric layer; patterning the dielectric layer to form a platform, an internal frame, an external frame and a hinge; and patterning the silicon substrate to separate it

into a platform unit, an internal frame unit and an external frame unit.

BRIEF DESCRIPTION OF THE DRAWINGS

The accompanying drawings, which are incorporated in and 5 constitute a part of the specification, illustrate an embodiment of the invention, and, together with the description, serve to explain the principles of the invention:

FIG. 1 shows an array antenna system;

FIG. 2(a) shows performance in the case of using a conventional 10 array antenna;

FIG. 2(b) shows performance in the case of using an array antenna that utilizes antennas according to a preferred embodiment of the present invention;

FIG. 3 shows a configuration of a beam steering antenna capable of 15 mechanical movements;

FIG. 4 shows a process for manufacturing a mechanical beam steering antenna according to a preferred embodiment of the present invention; and

FIG. 5 shows an arrangement of a magnetic body for magnetically 20 driving a mechanical beam steering antenna and a driving method according to a preferred embodiment of the present invention.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

In the following detailed description, only the preferred embodiment of the invention has been shown and described, simply by way of illustration of the best mode contemplated by the inventor(s) of carrying out the invention. As will be realized, the invention is capable of modification in various obvious respects, all without departing from the invention. Accordingly, the drawings and description are to be regarded as illustrative in nature, and not restrictive.

FIG. 2(a) shows each antenna's pattern, array factor and radiation pattern in the case of using a conventional array antenna system. FIG. 2(b) shows simulation results of each antenna's pattern, array factor and final radiation pattern in the case of configuring an array antenna using mechanically movable antennas, where the gap between the antennas is defined to be 1/2 wavelength, and the beam direction is set to be 45 degrees from the direction perpendicular to the antenna array if the number of the antennas is set to be '10.'

It is found from the simulation that the radiation pattern of FIG. 2(b) is better than that of FIG. 2(a). It shows that the case of mechanically moving the antenna so that the radiation side of the antenna is directed to the direction to which the beams will be sent has better beam characteristics.

FIG. 3 shows a configuration of a mechanically moving beam steering antenna.

A silicon substrate is attached on a glass substrate, and a ground plane is provided on the silicon substrate. A dielectric polymer layer (e.g., a BCB hinge) is formed on the ground plane, and a microstrip line connected to the antennas is formed on the dielectric polymer layer. A magnetic stick of 5 Ni is formed on the bottom surface of the silicon substrate.

The dielectric polymer layer includes a central platform, an internal frame and an external frame respectively surrounding the central platform, a pair of internal hinges for connecting the platform with the internal frame; and a pair of external hinges for connecting the internal frame with the external 10 frame. A plurality of antennas is arranged on the platform, and the microstrip line connected to the antennas is formed on the internal hinge and the frame. Two pairs of polymer hinges are formed, and one pair of hinges provided opposite to each other with respect to a patch antenna functions as a single 15 rotary shaft. That is, in the case where one pair of the internal hinges forms a rotary shaft for east-to-west rotations, the opposite pair of the external hinges forms a rotary shaft for south-north rotations. If the material of the hinges allows distortions of about almost 90 degrees, the antenna platform can steer the direction of the beams in all points in three-dimensional hemisphere space with respect to two rotary shafts.

20 The silicon substrate comprises a platform of the dielectric polymer layer; platform units respectively corresponding to the internal and external frames; an internal frame unit; and an external frame unit, and is combined

with the dielectric polymer layer to be varied with the dielectric polymer layer.

One pair of magnetic sticks is formed on the silicon substrate's platform units, and another pair of the magnetic sticks is formed on the internal frame unit. The magnetic sticks formed on the platform units are 5 formed in the direction parallel to that of the internal hinges, and the magnetic sticks formed on the internal frame unit are formed in the direction parallel to that of the external hinges.

The antenna uses a microstrip patch antenna structure. In this structure, it is more appropriate to use a microstrip feeding structure for the 10 mechanically moving antenna. Basically, the dielectric is used for the microstrip line and the patch antenna is used for a moving antenna structure by processing the dielectric through the micro electro mechanical systems (MEMS) technique. To manufacture the antenna, the bulk and surface micromachining technique of the MEMS is compositely used, and FIG. 4 15 shows a corresponding manufacturing process.

To prevent loss to the substrates, an anodic bonding process is performed on high-resistive silicon with low electric loss and on a glass wafer so as to use the process-performed ones as a substrate, and a bulk micromachining technique is executed on them to obtain a space for 20 mechanical rotation. The high-resistive silicon is processed to be thin to protect the mechanical deformation of the polymer dielectric. A ground line, polymer dielectric and a microstrip patch are sequentially formed on the front

surface of the silicon substrate, and the ground line and the microstrip patch are manufactured through an electroplating method using a polymer mold. The polymer dielectric is manufactured into the form of an antenna through a plasma etching process, and penetration etching is performed on a 5 predetermined portion of the silicon substrate needed for moving the structure. Accordingly, the antenna platform is separated from the substrate and becomes rotatable.

In order to enlarge beam-scanning ranges, the rotation of wide angles is needed. In general, in the case of electrostatic driving used in the 10 MEMS structure, greater driving power is generated when the distance between a driving electrode and the structure becomes shorter, and in this instance, the movement of the structure is restricted according to contact with the electrode. To solve this problem in the present invention, a magnetic force driving method is used. For this, as shown in FIG. 4(c), the rear surface 15 of the silicon substrate is electroplated with magnetic material such as nickel by using the electroplating method utilizing the polymer mold, and magnetic fields are provided from the bottom portion. FIG. 5 shows an arrangement of the magnetic material and a principle of rotation driving. As shown, when a uniform magnetic field is provided to the magnetic material from a solenoid 20 coil, a force for magnetization vectors caused by magnetic anisotropy within the magnetic material to be arranged in parallel with the direction of the magnetic field is generated. This magnetic force generates a rotation torque

according to the hinge structure so that the structure rotates with respect to the rotation axis in parallel to the hinge.

In the case where only the patch is moved, it is difficult to make a feeding structure having an appropriate impedance matching since the 5 impedance is greatly varied, and hence, the dielectric under the patch must be concurrently moved. In this instance, to obtain a wide driving angle, the mechanical characteristics of the hinge structure are important, and by using the material of low elasticity such as the polymer dielectric for the hinge, distortion driving is easily obtained. By using the MEMS technique, it is 10 possible to precisely process the above-described small structure, and fast mechanical responses are obtained through the minimization.

According to the present invention, by providing electrical phase differences to the respective antennas, the beams can be steered in the desired directions, and by mechanically moving the antenna in the desired 15 direction, the performance of the antenna can be maximized regardless of the target's direction. By using this array antenna, a very effective system can be configured in the smart antenna. That is, when this antenna is used as a receiving antenna, because of its good efficiency, receiving performance can be improved regardless of the receiving angles in the case 20 of using a transmitter that generates less power. Also, when this antenna is used as a transmitting antenna, full signals can be transmitted to desired directions regardless of the angles with less power.

While this invention has been described in connection with what is presently considered to be the most practical and preferred embodiment, it is to be understood that the invention is not limited to the disclosed embodiments, but, on the contrary, is intended to cover various modifications and equivalent arrangements included within the spirit and scope of the appended claims.

WHAT IS CLAIMED IS:

1. An antenna device comprising:
 - an antenna;
 - 5 a first rotation shaft for enabling angular displacements of the antenna in the first direction; and
 - a second rotation shaft for enabling angular displacements of the antenna in the second direction independent from the angular displacements of the antenna in the first direction.
- 10 2. The antenna device of claim 1, wherein further comprising:
 - a platform for supporting the antenna;
 - an internal frame connected to the platform through the first rotation shaft;
 - 15 an external frame connected to the platform through the second rotation shaft;
 - a ground plane formed on a surface opposite to a surface on which the antenna of the platform is formed;
 - a first conductive line connected to the antenna; and
 - a second conductive line connected to the ground plane.
- 20 3. The antenna device of claim 2, further comprising a driver for mechanically displacing the platform and the internal frame using electromagnetic force.
4. A method for manufacturing an antenna device comprising:

5

attaching a silicon substrate to a glass substrate;
processing the glass substrate to form a displacement space;
forming a ground plane on the silicon substrate;
forming a dielectric layer on the ground plane;
forming an antenna on the dielectric layer;
patterning the dielectric layer to form a platform, an internal frame,
an external frame and a hinge; and
patterning the silicon substrate to separate it into a platform unit, an
internal frame unit and an external frame unit.

10

1/5

FIG. 1

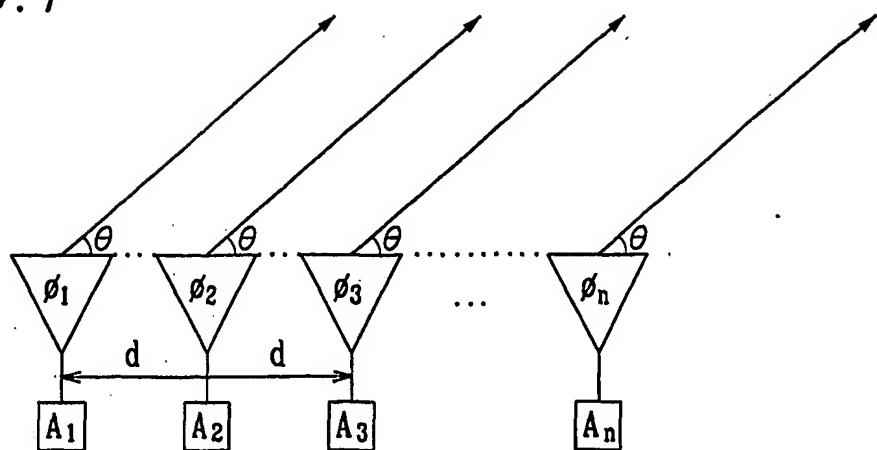


FIG. 2A

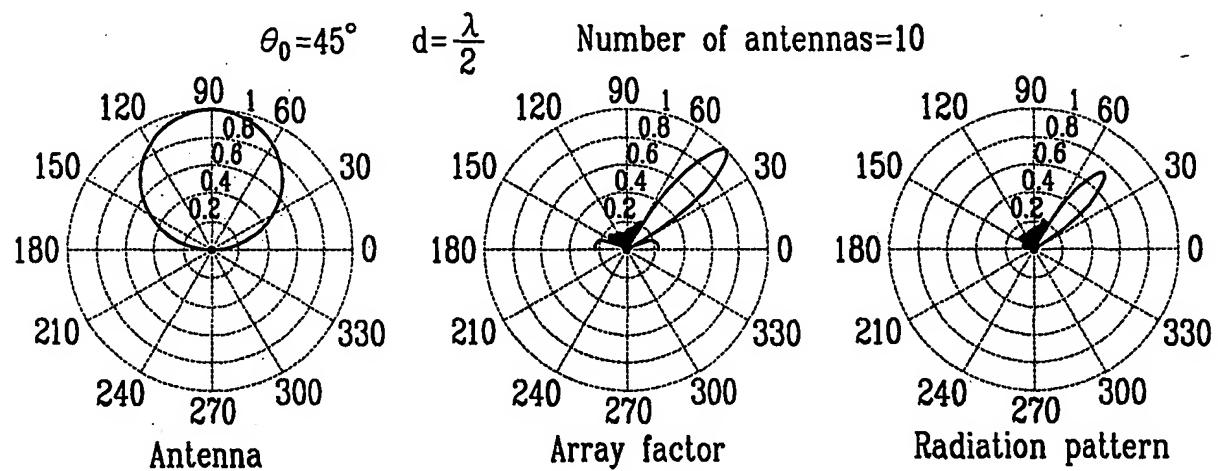
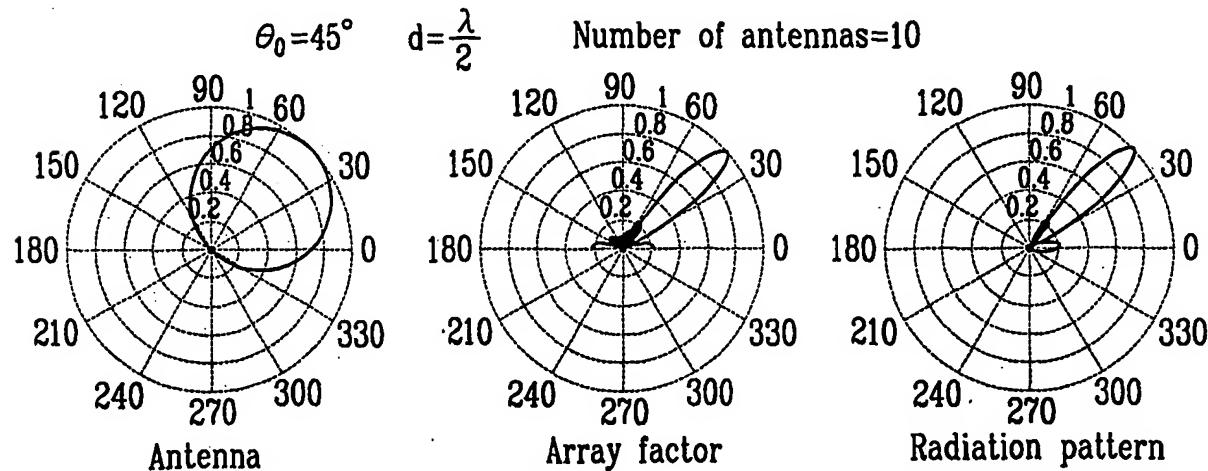
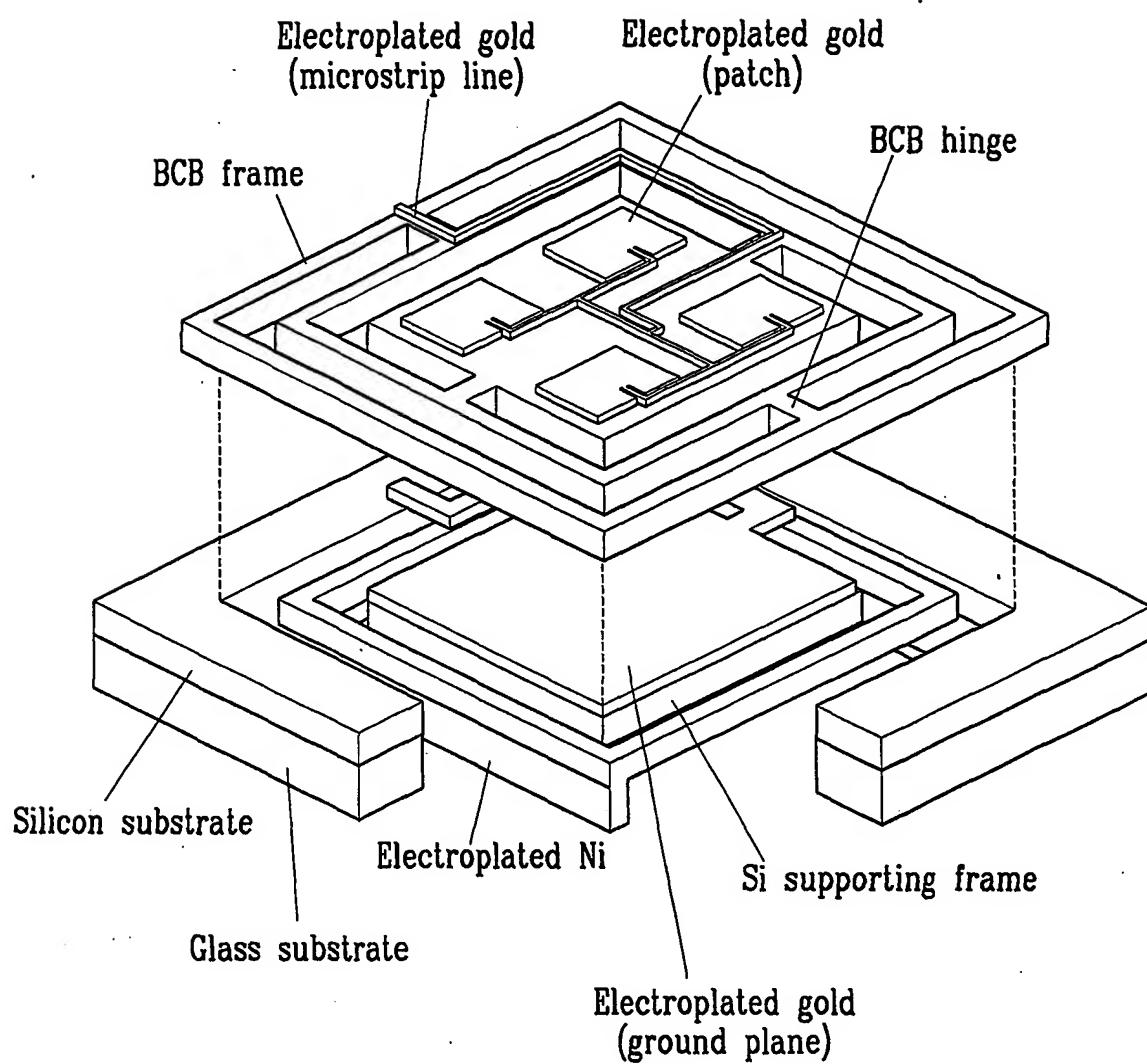


FIG. 2B



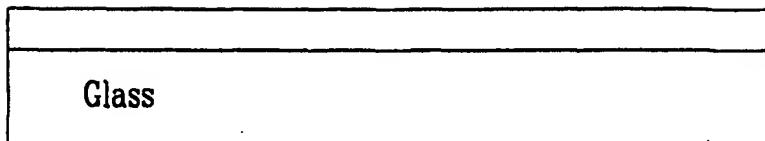
2/5

FIG. 3



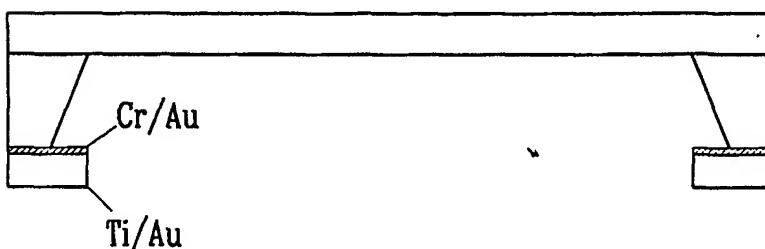
3/5

FIG. 4A



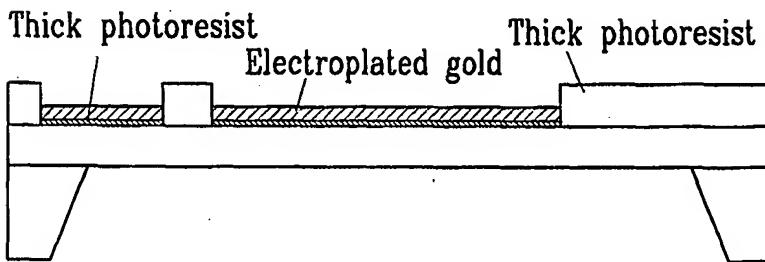
- * Anodic bonding of glass & silicon
- * Thinning of silicon using KOH
- * CMP of silicon

FIG. 4B



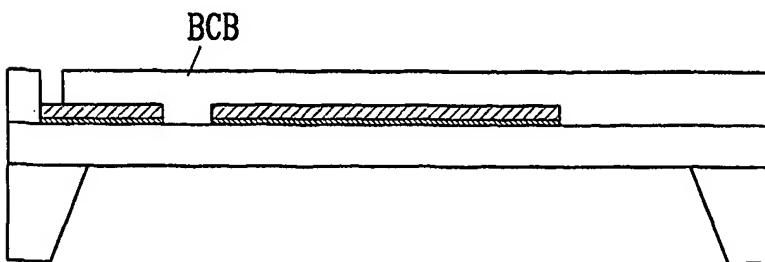
- * Cr/Au deposition
- * Photolithography #1
- * Au/Cr etch
- * Hardbake of photoresist
- * Glass etching

FIG. 4C



- * 1st seed layer deposition
- * Photolithography #2
- * Electroplating

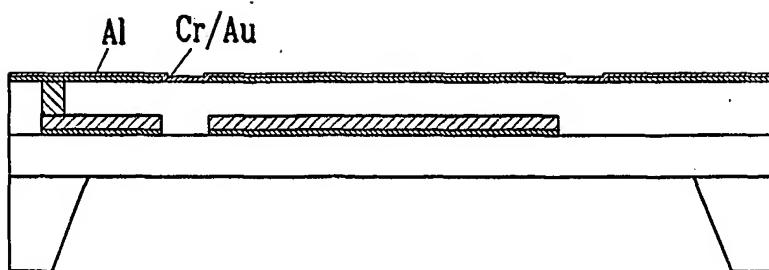
FIG. 4D



- * PR strip
- * Seed layer etching
- * BCB coating & baking
- * BCB patterning

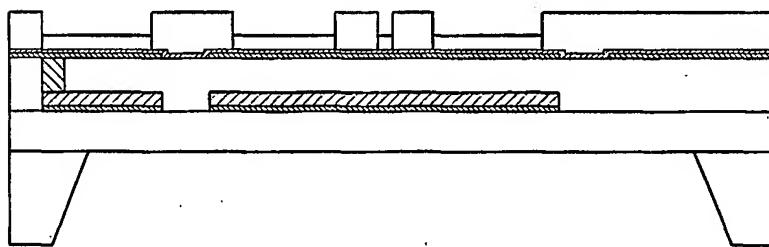
4/5

FIG. 4E



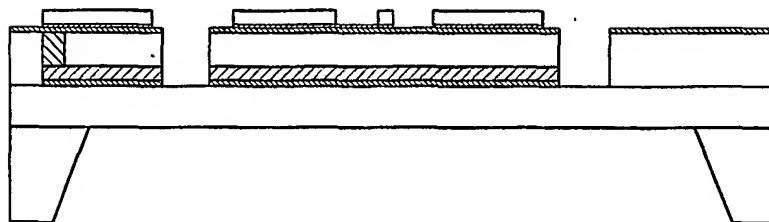
- * Au electroplating (for via)
- * Al mask deposition
- * Photolithography #3
- * Al etching
- * 2nd seed layer deposition

FIG. 4F



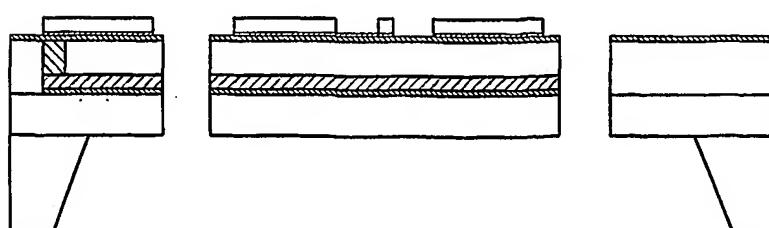
- * Photolithography #4
- * Au electroplating

FIG. 4G



- * PR strip
- * Seed layer etching
- * RIE of BCB

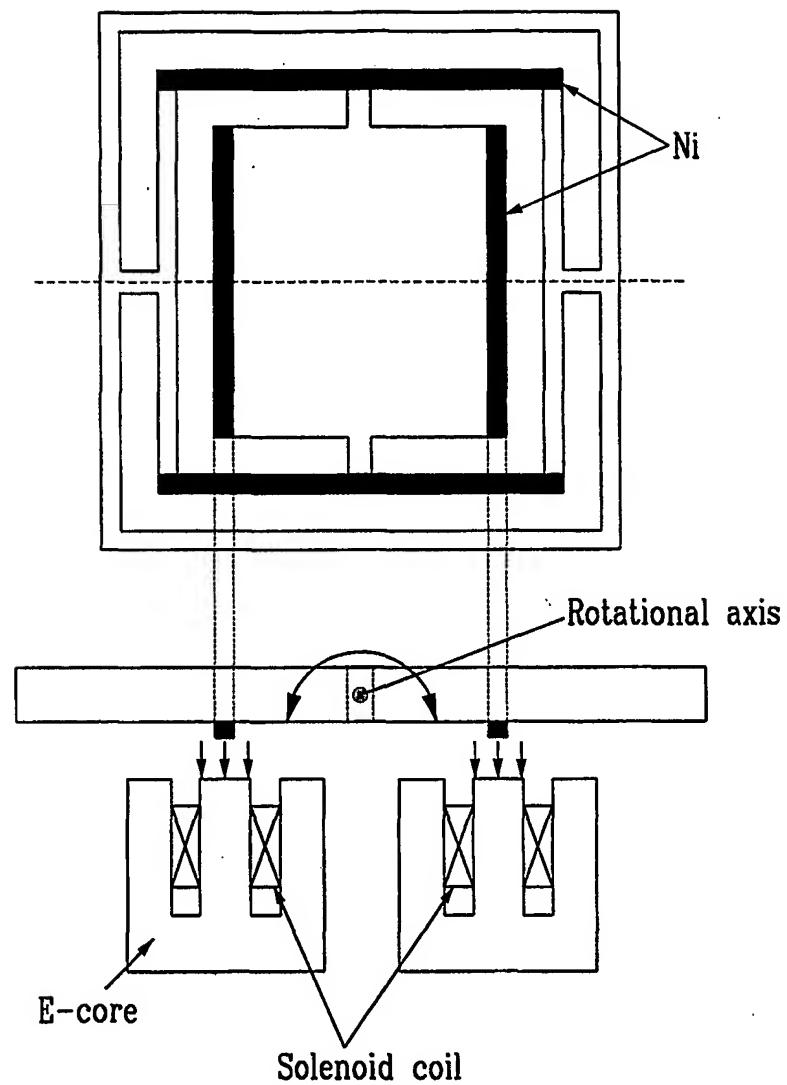
FIG. 4H



- * Silicon deep RIE

5/5

FIG. 5



INTERNATIONAL SEARCH REPORT

International application No.

PCT/KR01/01391

A. CLASSIFICATION OF SUBJECT MATTER

IPC7 H01Q 3/26

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

G01C19/00 G03F7/00

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Korean Patents and applicants for inventions since 1975

Korean Utility models and applicants for Utility models since 1975

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

FPD, PAJ, PAYROM, IEL(IEEE/IEE Library) Search

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	E. Brown, "RF-MEMS Switches for Reconfigurable Integrated Circuits," IEEE Trans. MTT, V.46, No.11, pp.1868, 1998	1
A	J.-C. Chiao et al, "MEMS Reconfigurable Vee Antenna," IEEE MTT IMS '99 (13, June, 1999)	1
A	Norvell, B. R et al, "Micro electro mechanical switch (MEMS) technology applied to electronically scanned arrays for space based radar," IEEE Proceedings (6, March, 1999)	1

Further documents are listed in the continuation of Box C.

See patent family annex.

* Special categories of cited documents:

"A" document defining the general state of the art which is not considered to be of particular relevance

"E" earlier application or patent but published on or after the international filing date

"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of citation or other special reason (as specified)

"O" document referring to an oral disclosure, use, exhibition or other means

"P" document published prior to the international filing date but later than the priority date claimed

"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

"Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art

"&" document member of the same patent family

Date of the actual completion of the international search

04 JANUARY 2002 (04.01.2002)

Date of mailing of the international search report

07 JANUARY 2002 (07.01.2002)

Name and mailing address of the ISA/KR

Korean Intellectual Property Office
Government Complex-Daejeon, Dunsan-dong, Seo-gu, Daejeon
Metropolitan City 302-701, Republic of Korea

Faxsimile No. 82-42-472-7140

Authorized officer

PARK, Chong Han

Telephone No. 82-42-481-5713



INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No.

PCT/KR01/01391

Patent document cited in search report	Publication date	Patent family member(s)	Publication date
E. Brown, "RF-MEMS Switchs for Reconfigurable Integrated Circuits," IEEE Trans. MTT, V.46, No.11	1998	NONE	
J.-C. Chiao et al, "MEMS Reconfigurable Vee Antenna," IEEE MTT IMS '99	13, June, 1999	NONE	
Norvell, B. R et al, "Micro electro mechanical switch (MEMS) technology applied to electronically scanned arrays for space based radar," IEEE Proceedings	6, March, 1999	NONE	